

FIG. 1

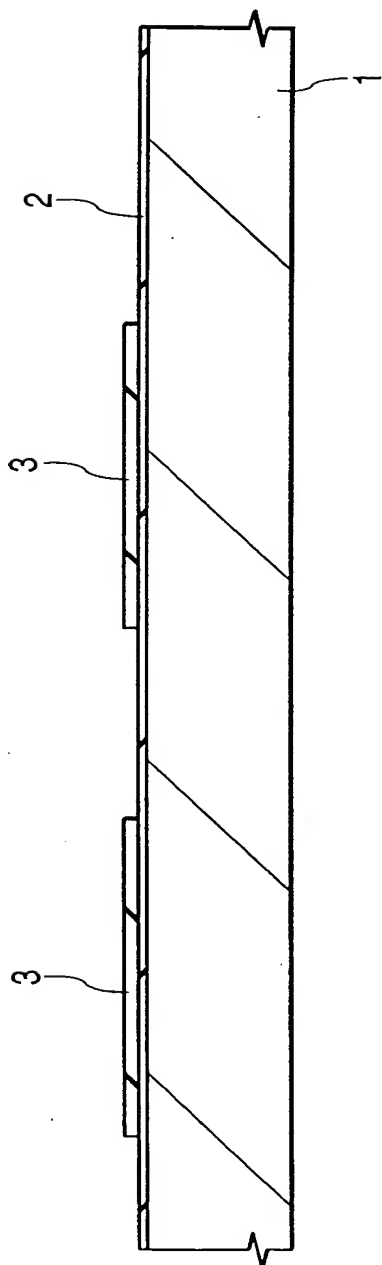


FIG. 2

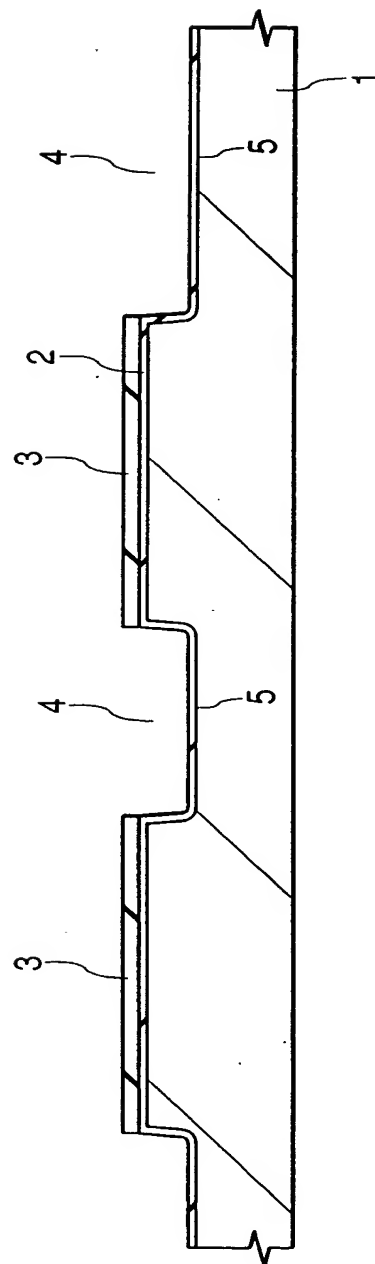


FIG. 3

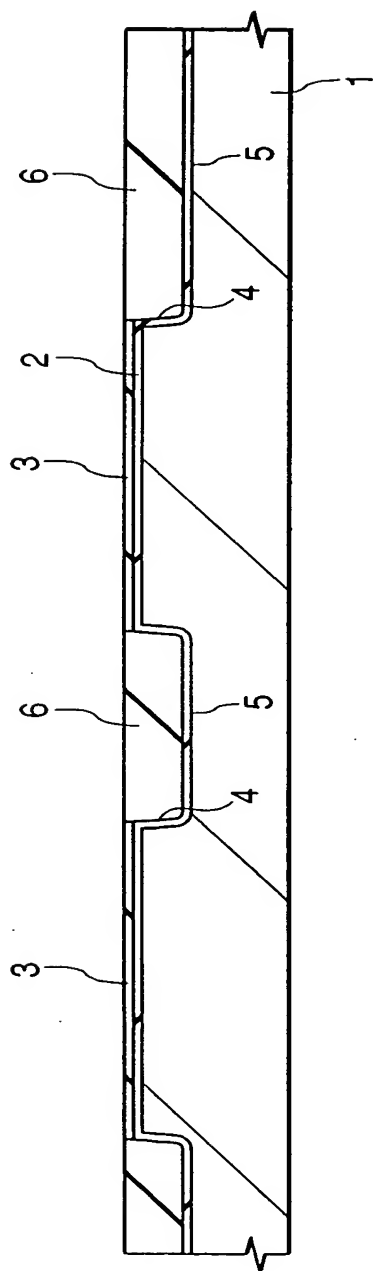


FIG. 4

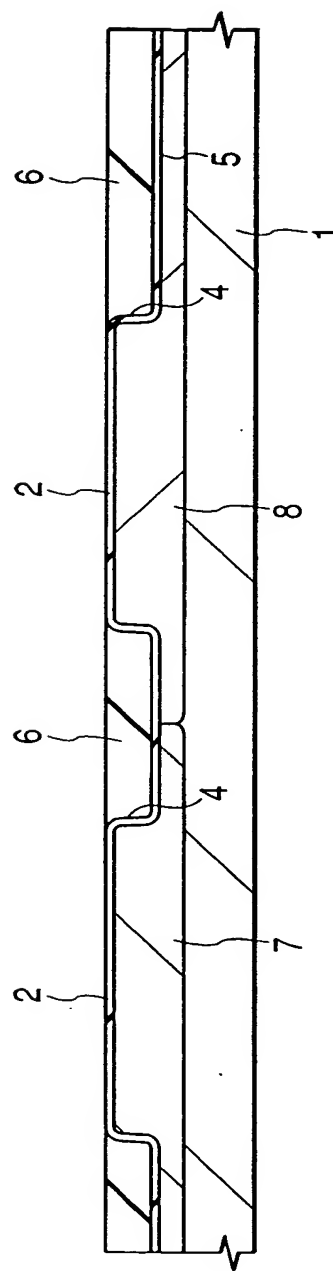


FIG. 5

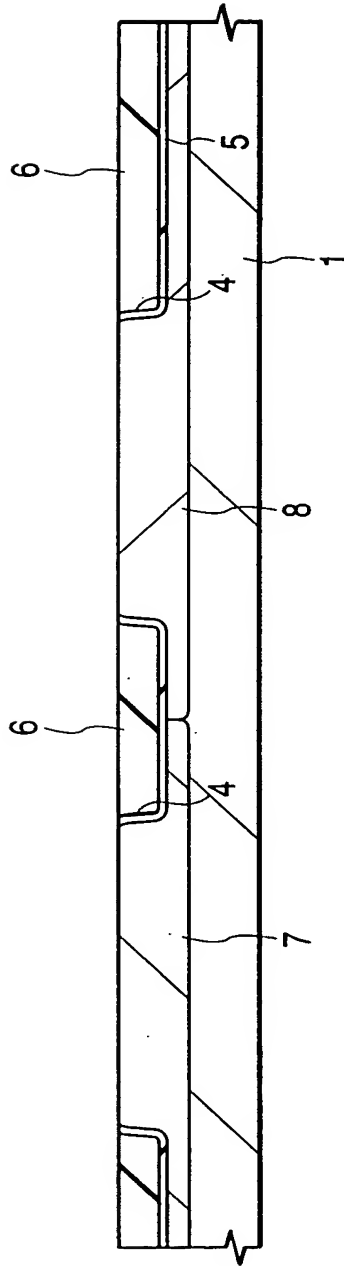


FIG. 6

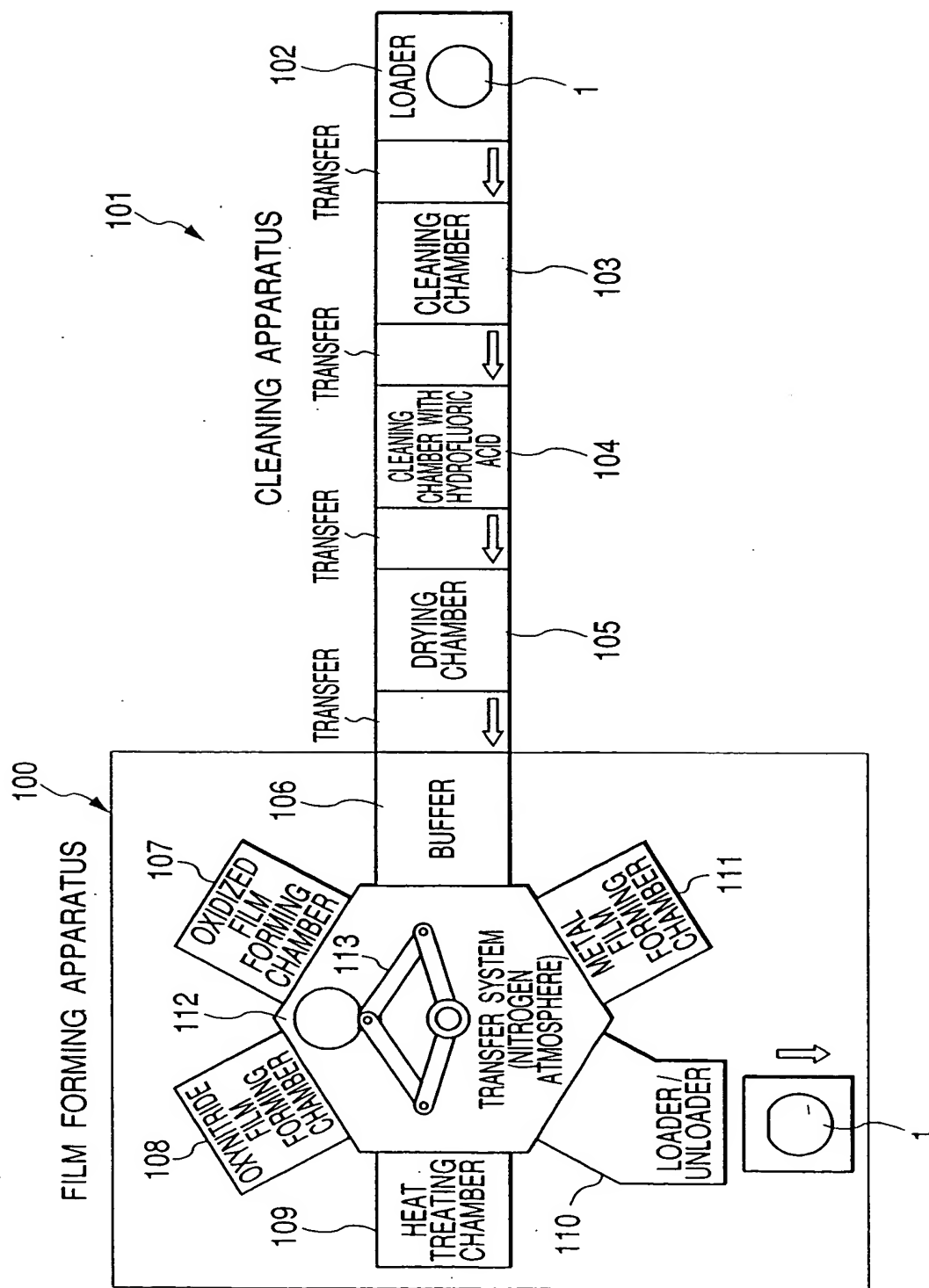


FIG. 7(a)

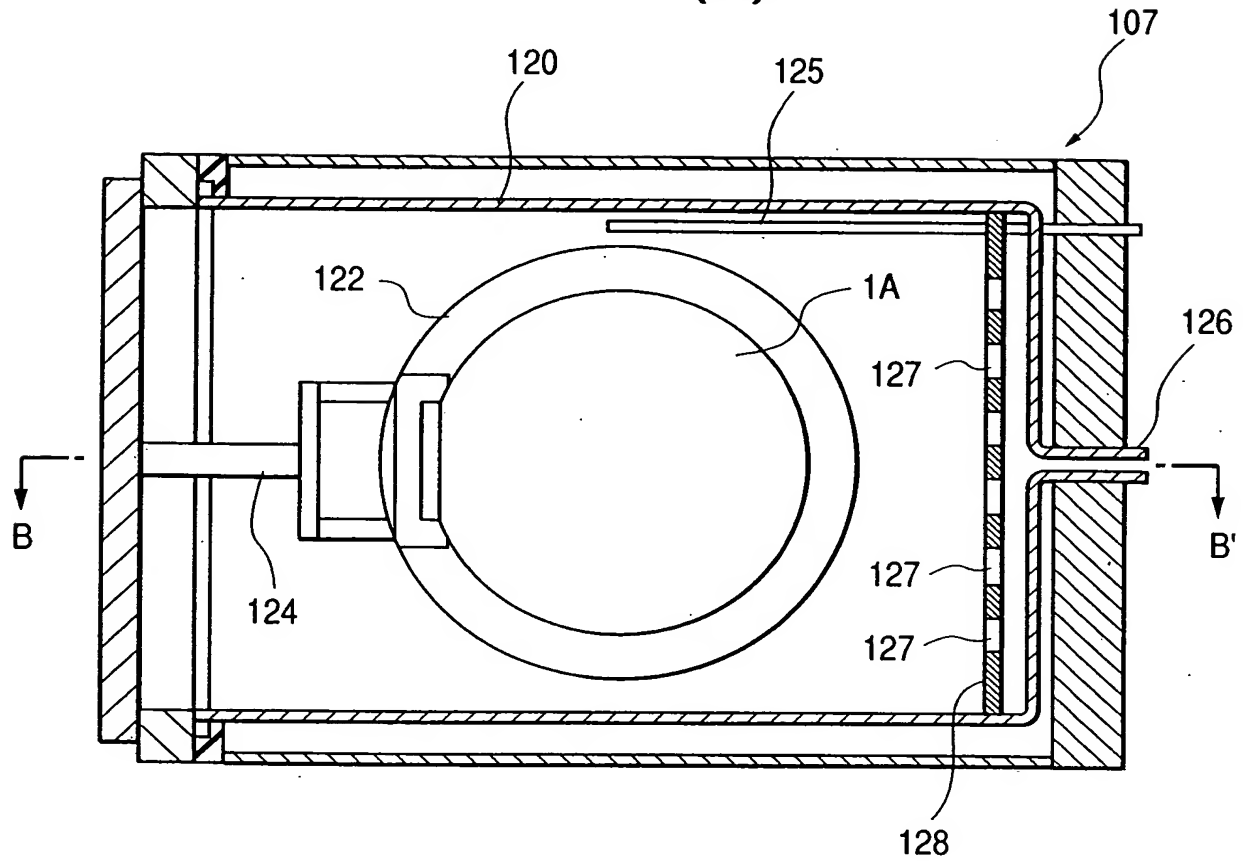


FIG. 7(b)

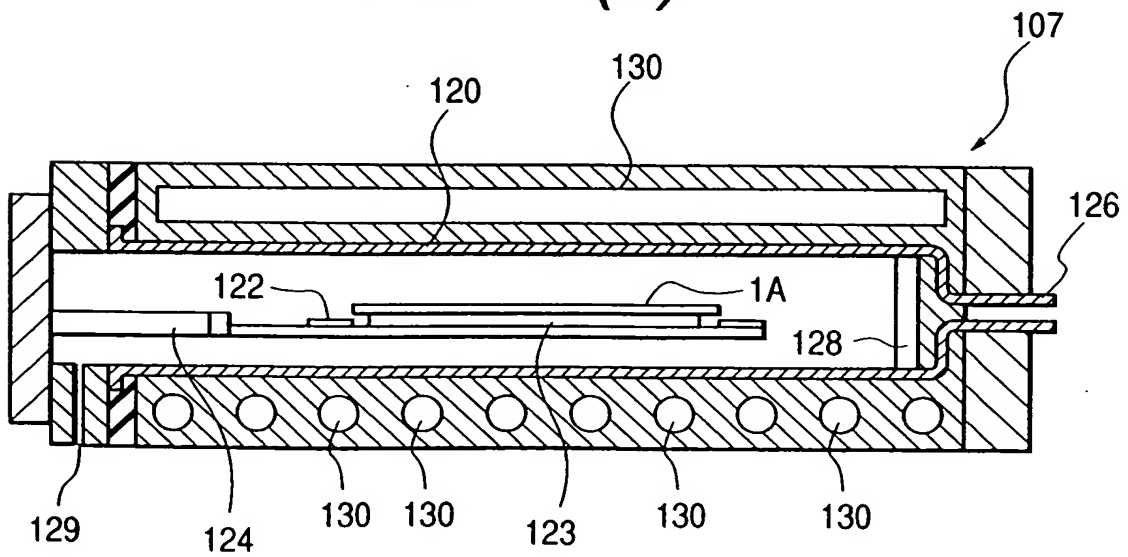


FIG. 8

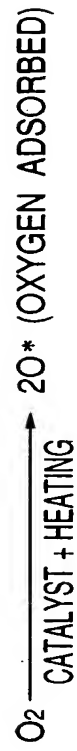
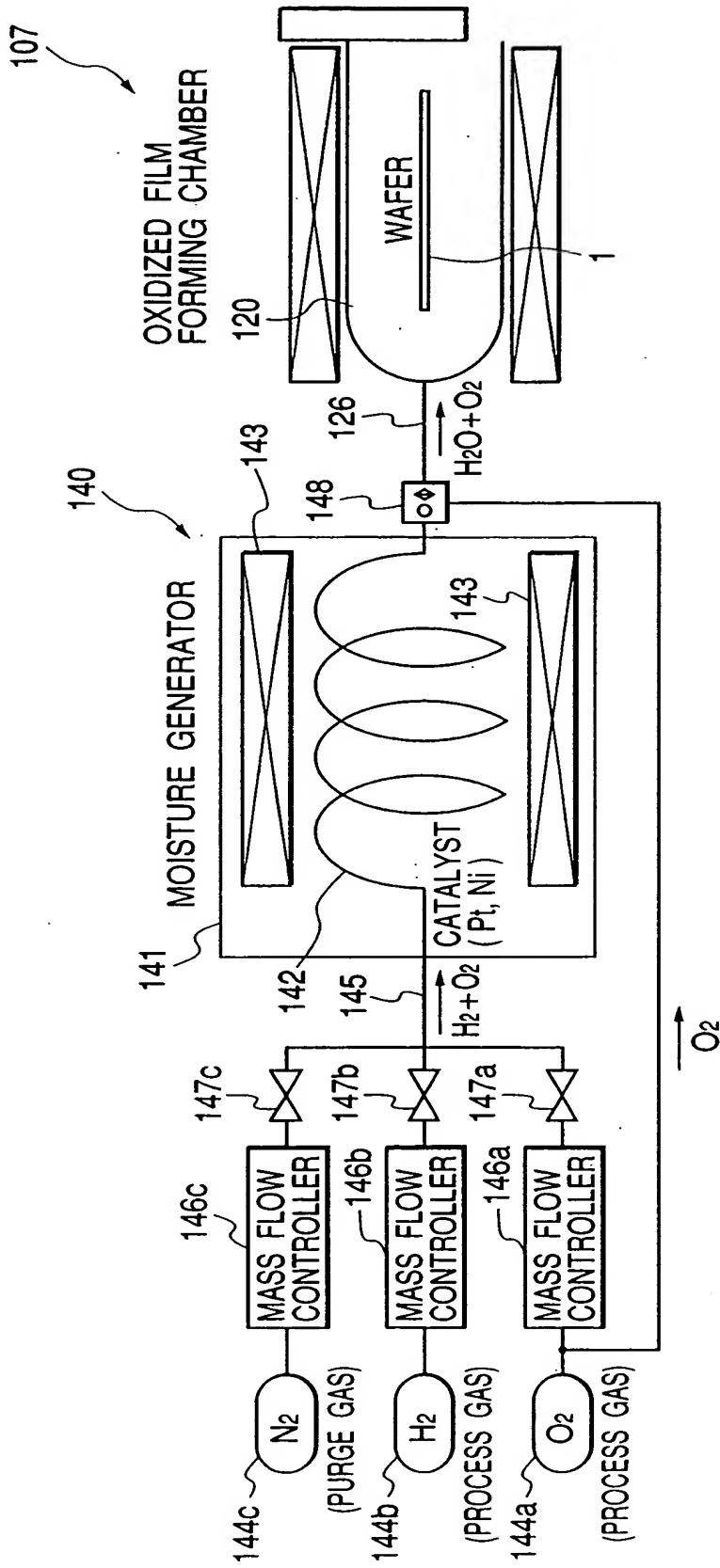


FIG. 9

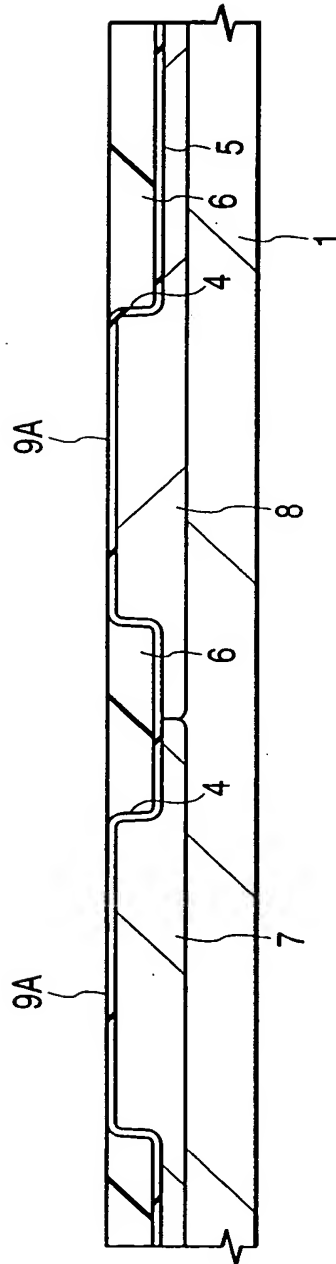


FIG. 10

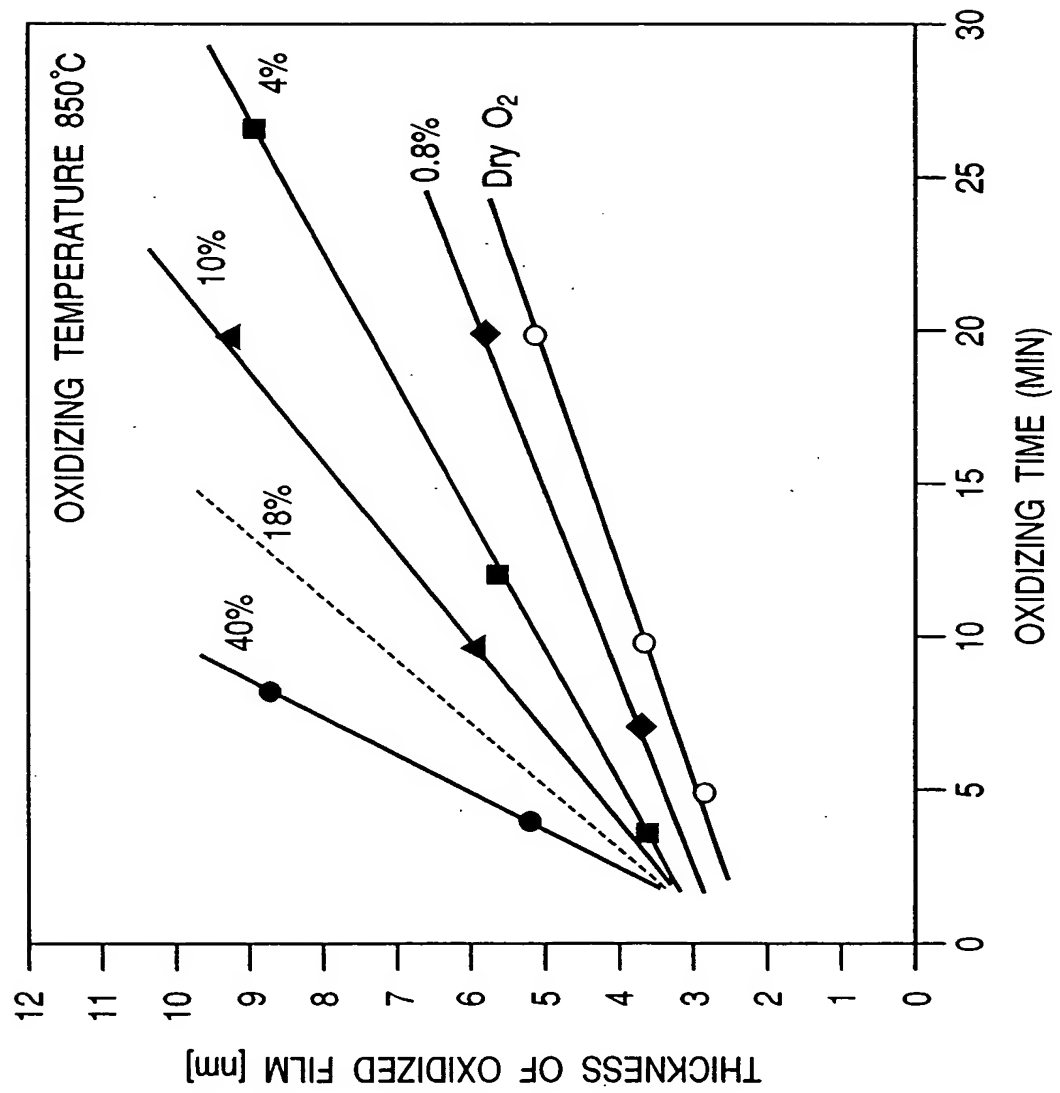


FIG. 11(a)

MOISTURE + OXYGEN GAS MIXTURE

F_w (FLOW RATE OF MOISTURE)
F_o (FLOW RATE OF OXYGEN)

FIG. 11(b)

MOISTURE + HYDROGEN GAS MIXTURE

P_w (PARTIAL PRESSURE OF MOISTURE)
P_h (PARTIAL PRESSURE OF HYDROGEN)

$$\text{MOISTURE CONCENTRATION} = \frac{F_w}{F_o + F_w} \times 100\%$$

$$\text{MOISTURE CONCENTRATION} = \frac{P_w}{P_h} \times 100\%$$

FIG. 12

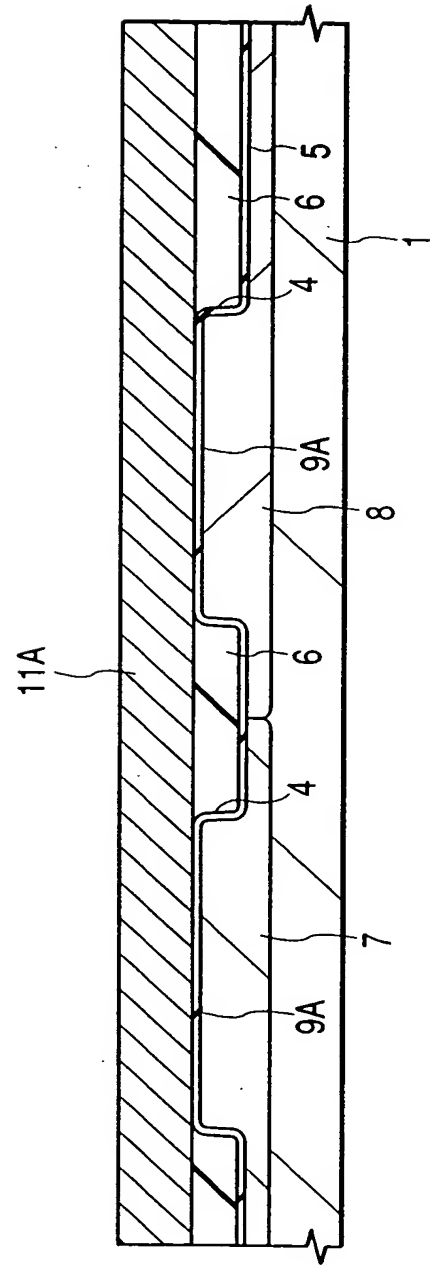


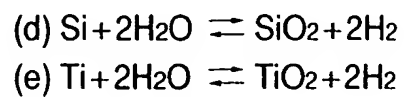
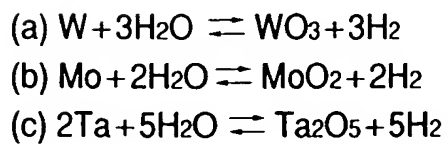
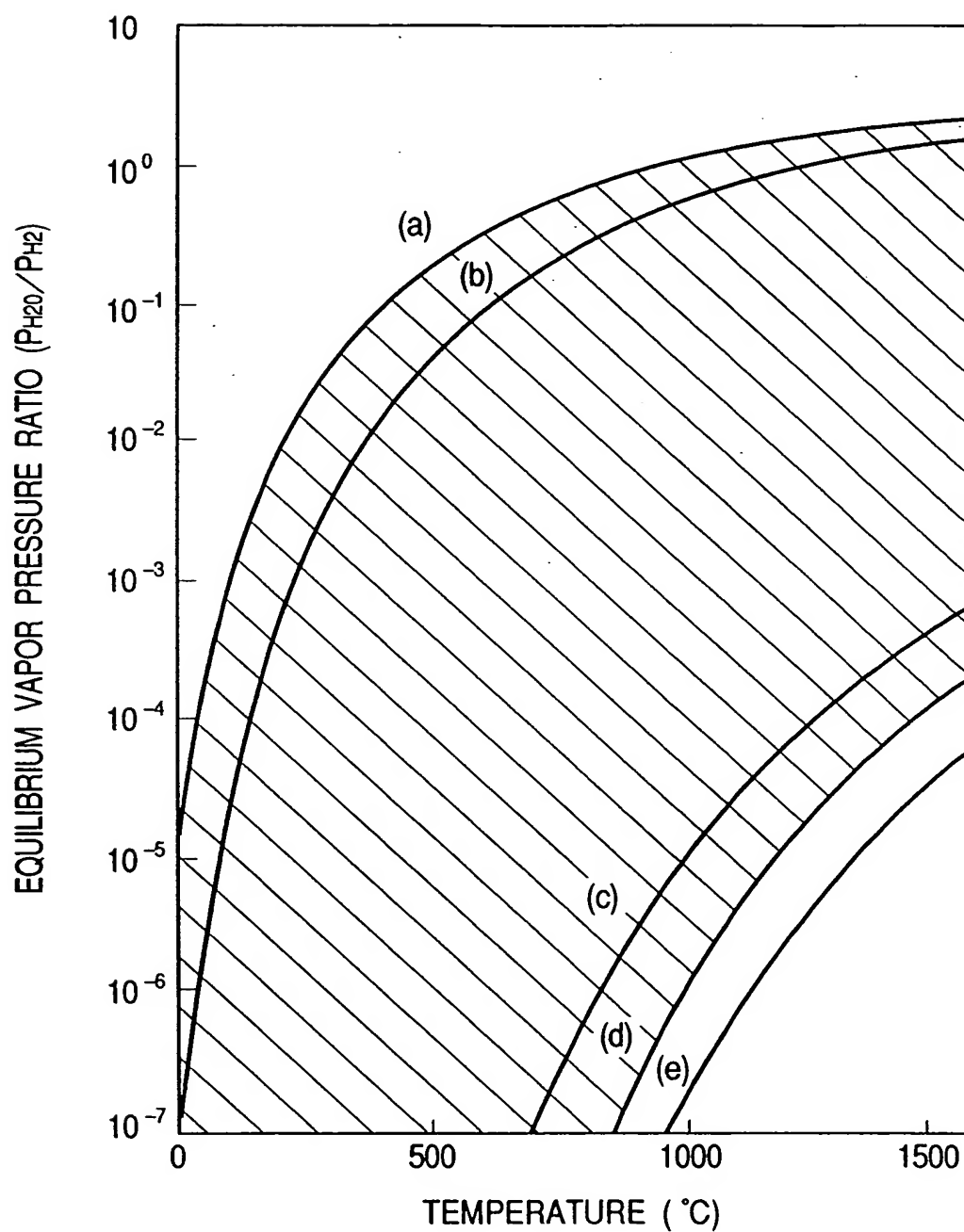
FIG. 13

FIG. 14

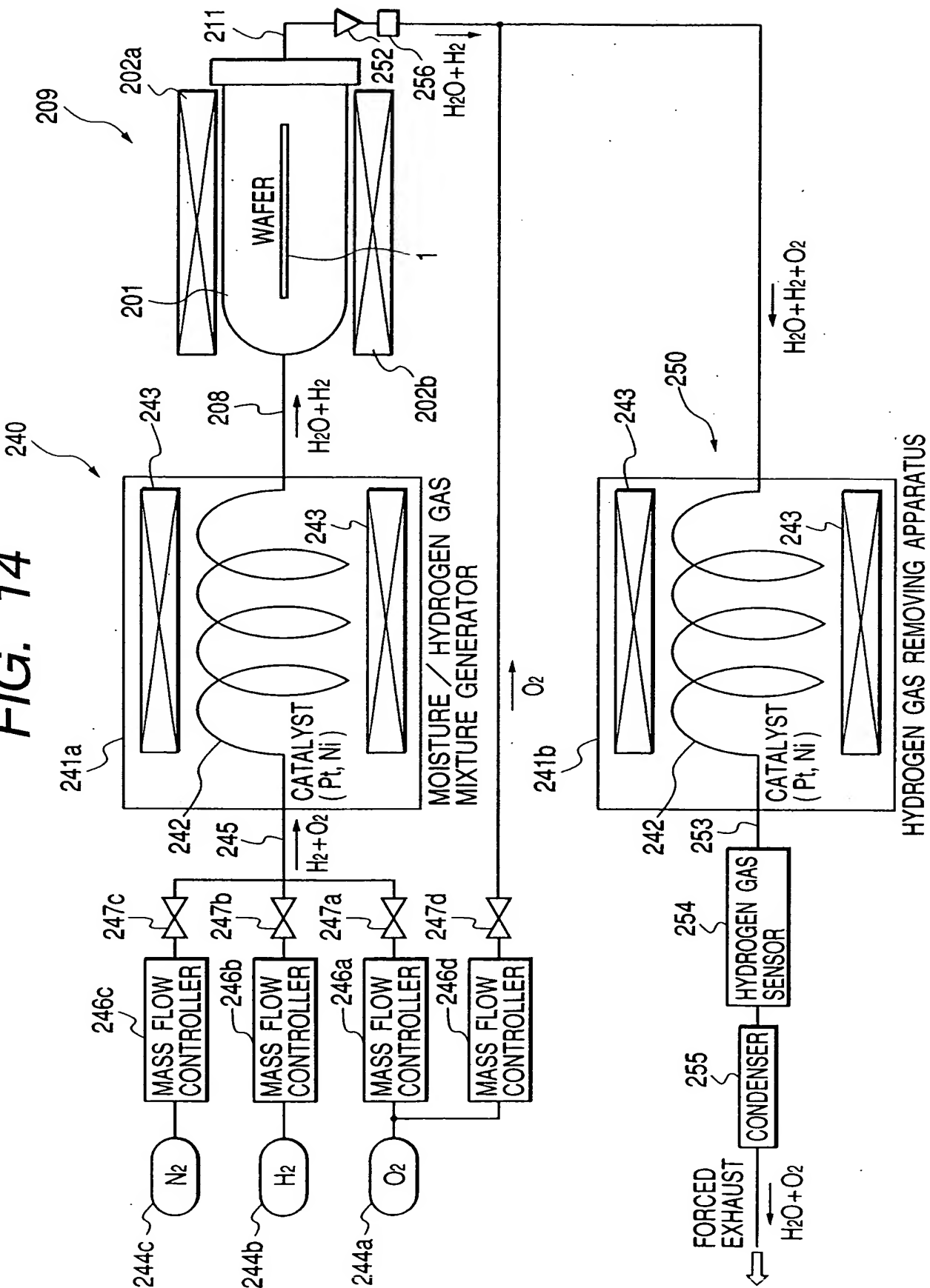


FIG. 15

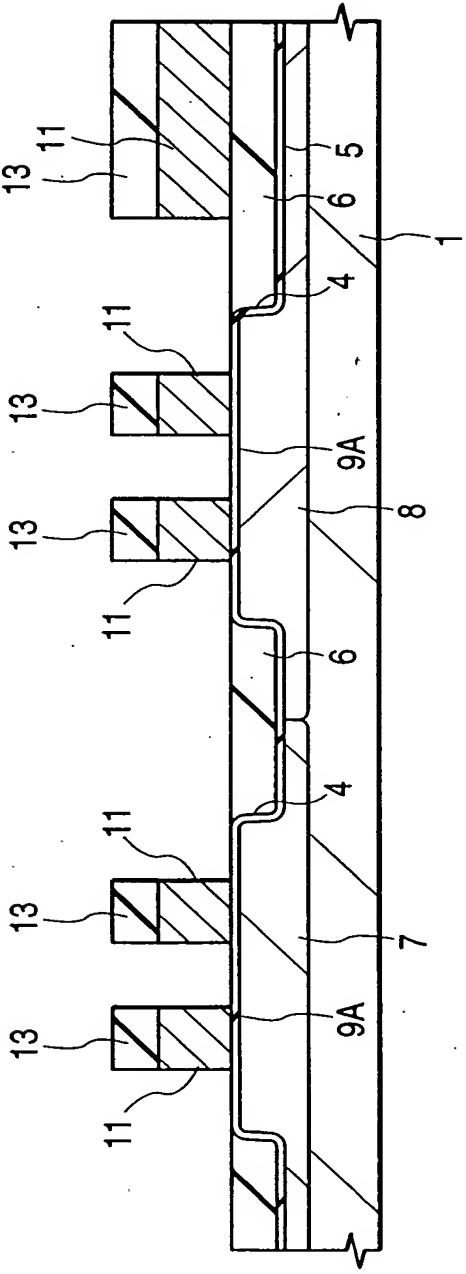


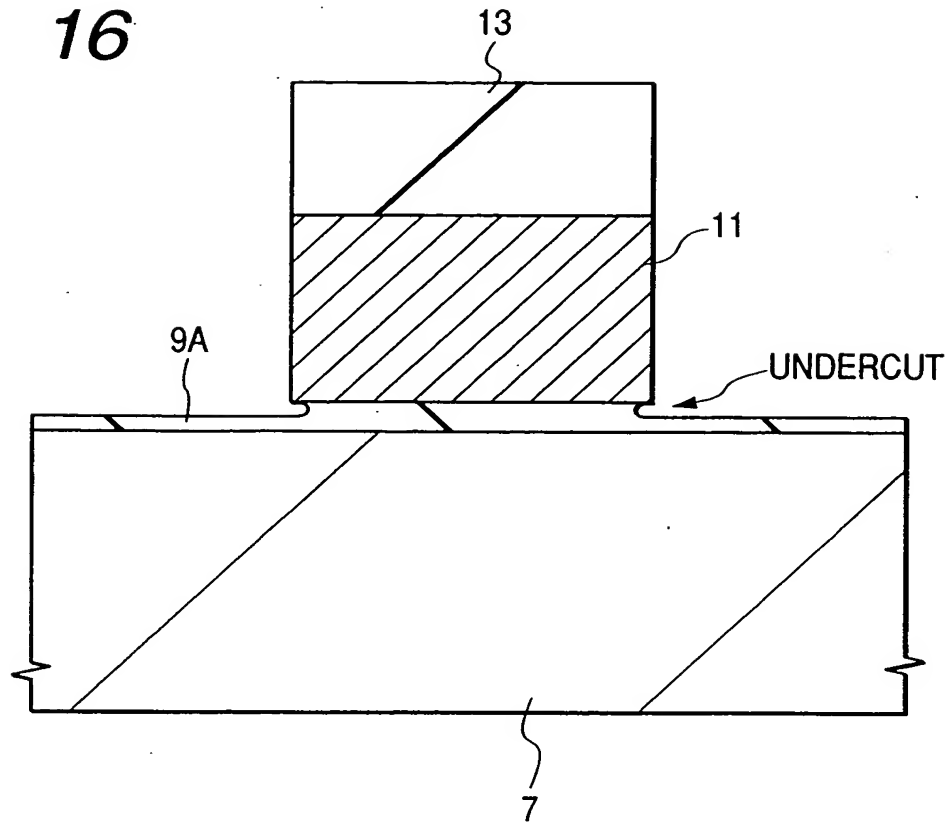
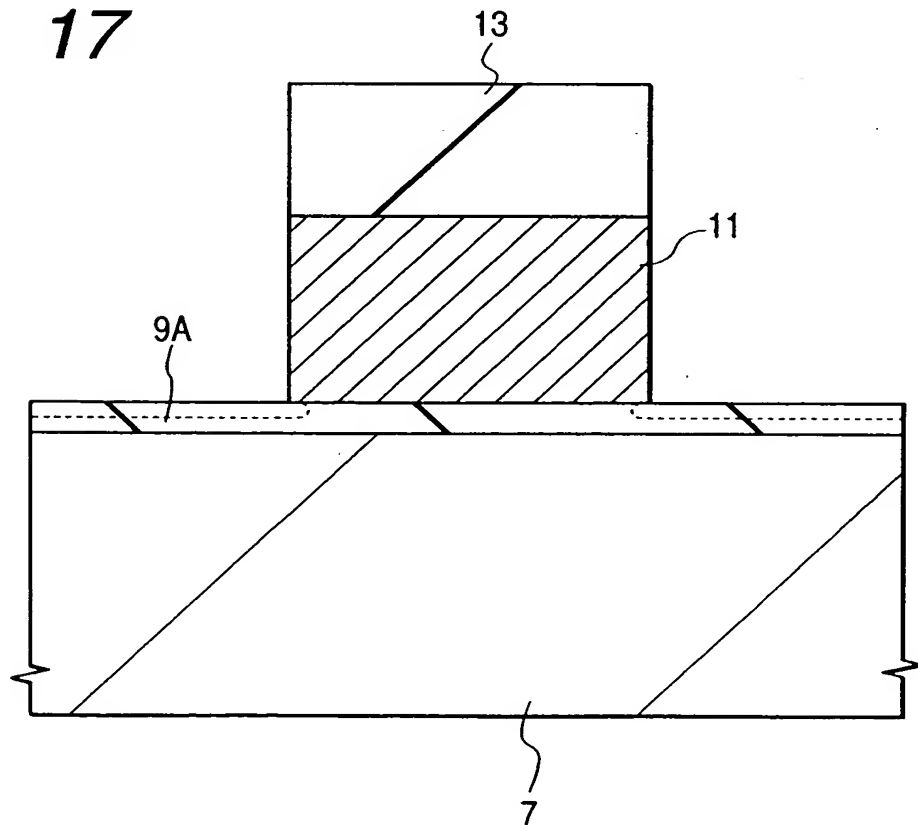
FIG. 16**FIG. 17**

FIG. 18

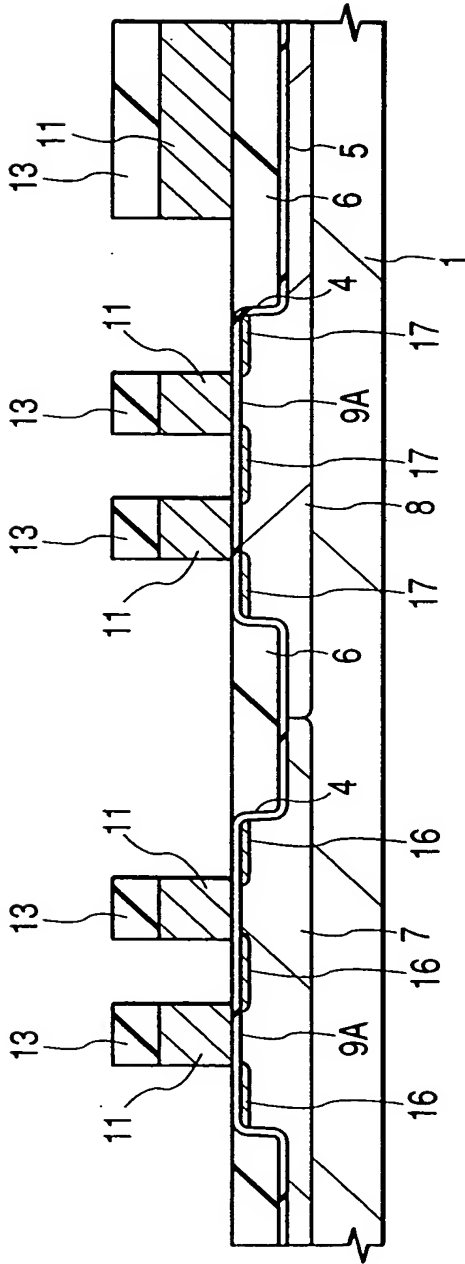


FIG. 19

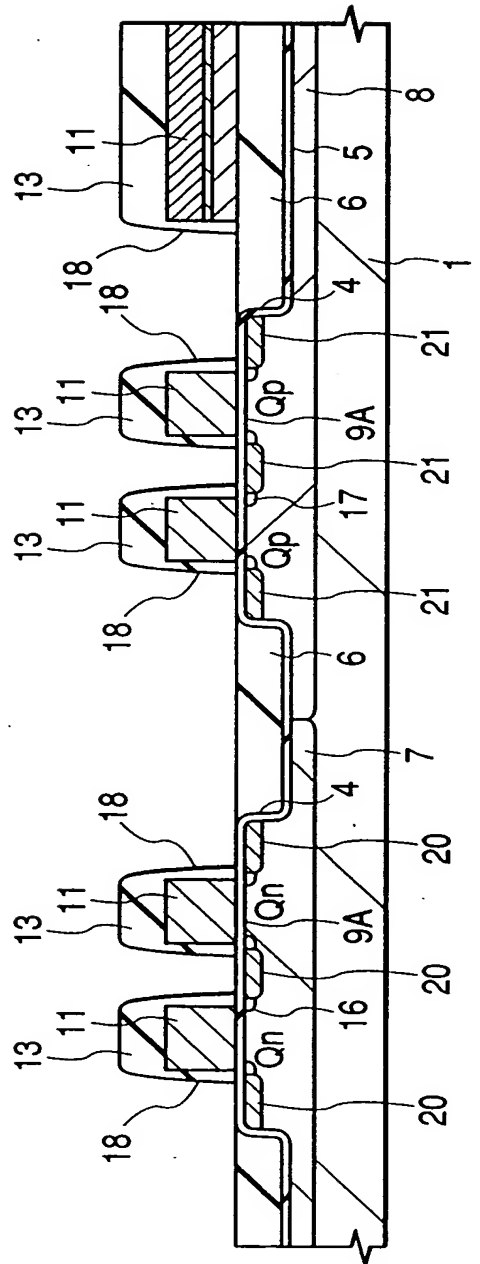


FIG. 20

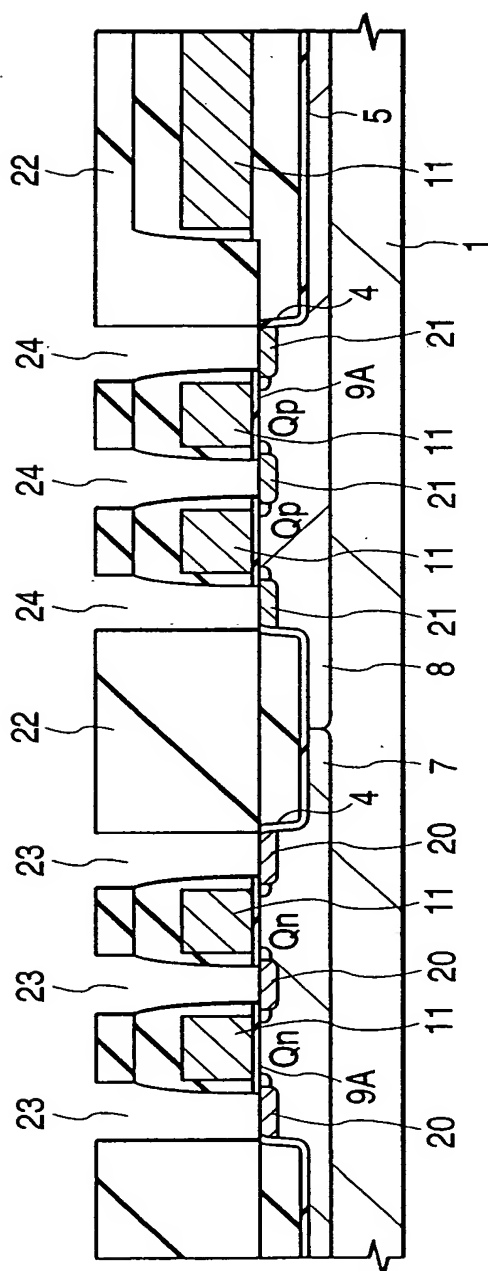


FIG. 21

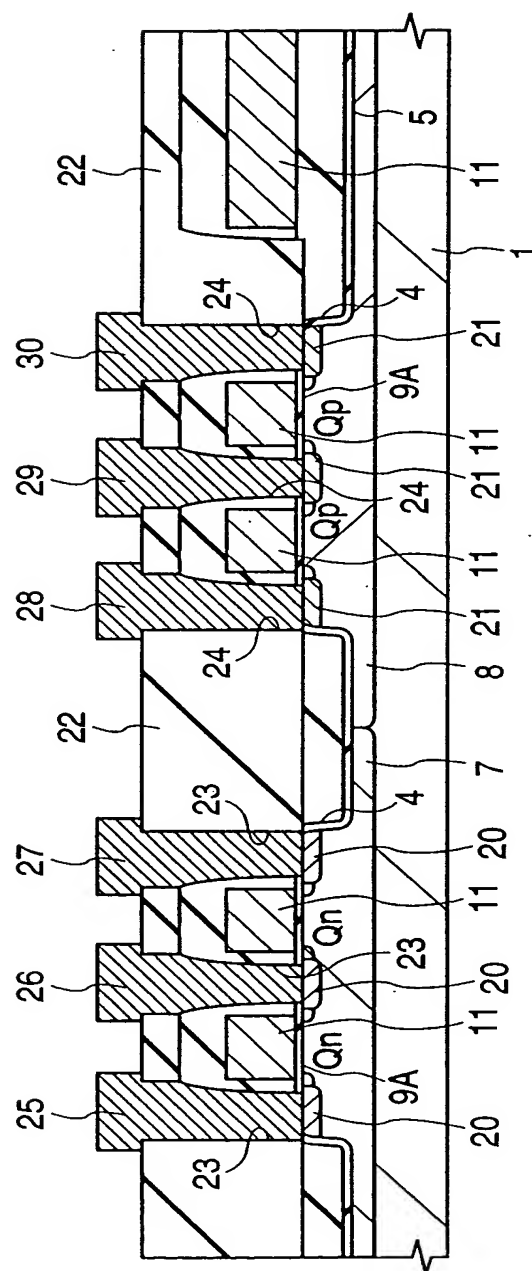


FIG. 22

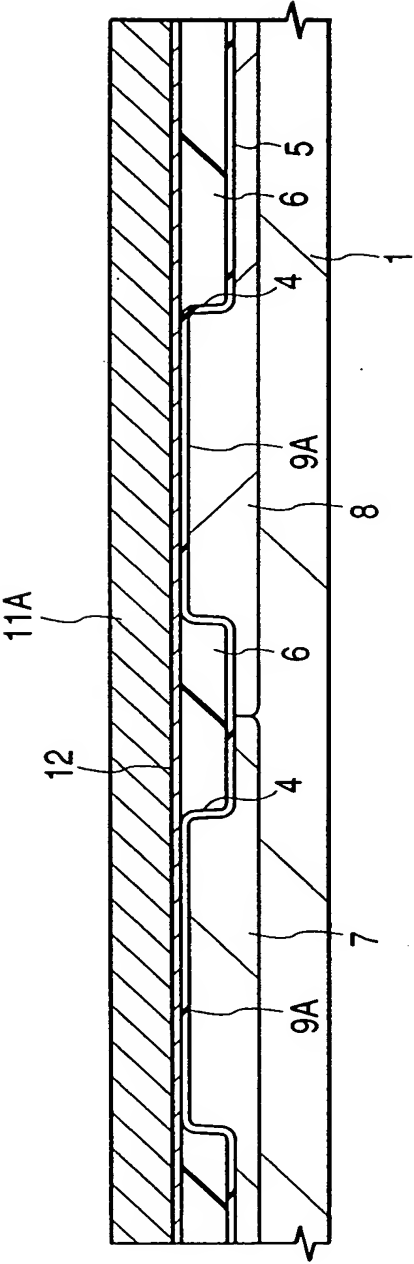


FIG. 23

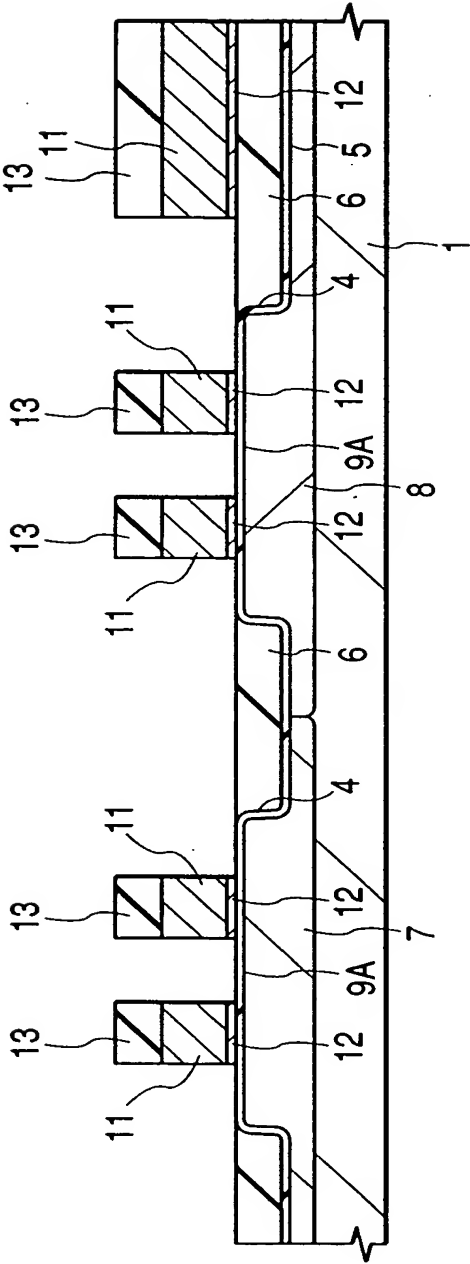


FIG. 24

d_r =EFFECTIVE FILM THICKNESS IN SiO_2 TERMS

d_i =THICKNESS OF TARGET INSULATING FILM

ϵ_s =DIELECTRIC CONSTANT OF SILICON

ϵ_i =DIELECTRIC CONSTANT OF TARGET INSULATING FILM

$$d_r = \epsilon_s \sum_i \frac{d_i}{\epsilon_i}$$

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FIG. 25

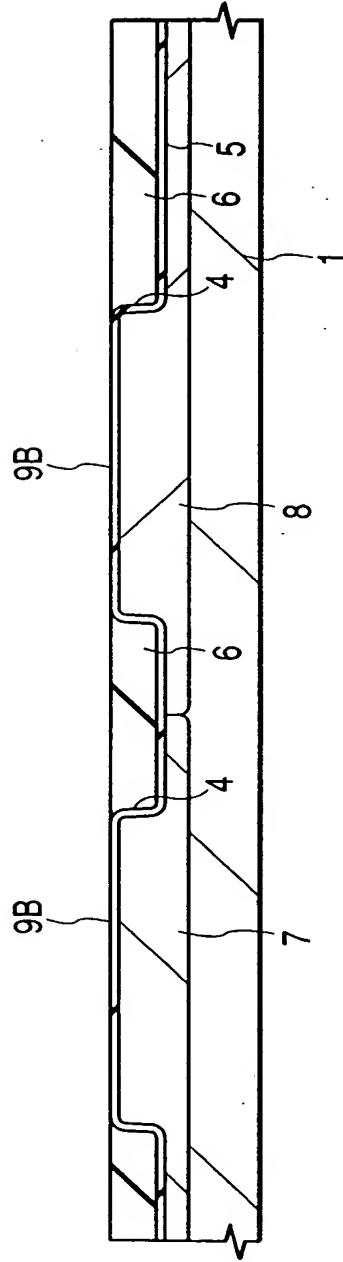


FIG. 26

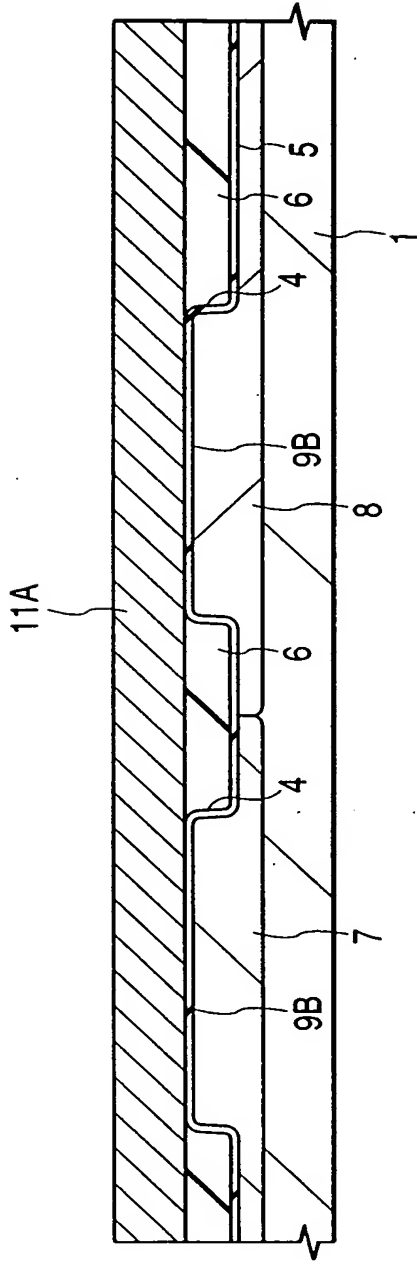


FIG. 27

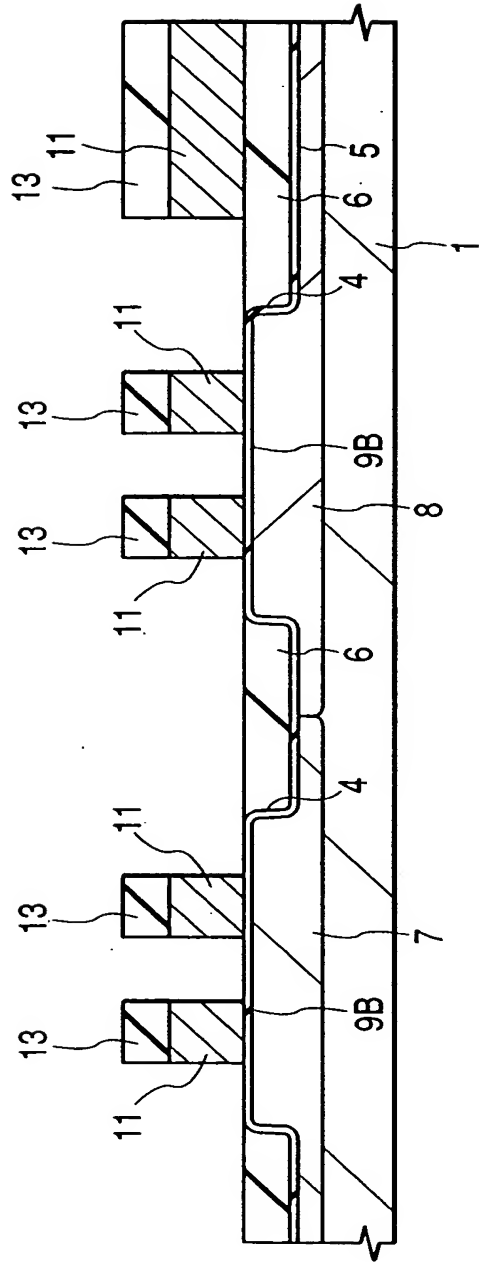


FIG. 28

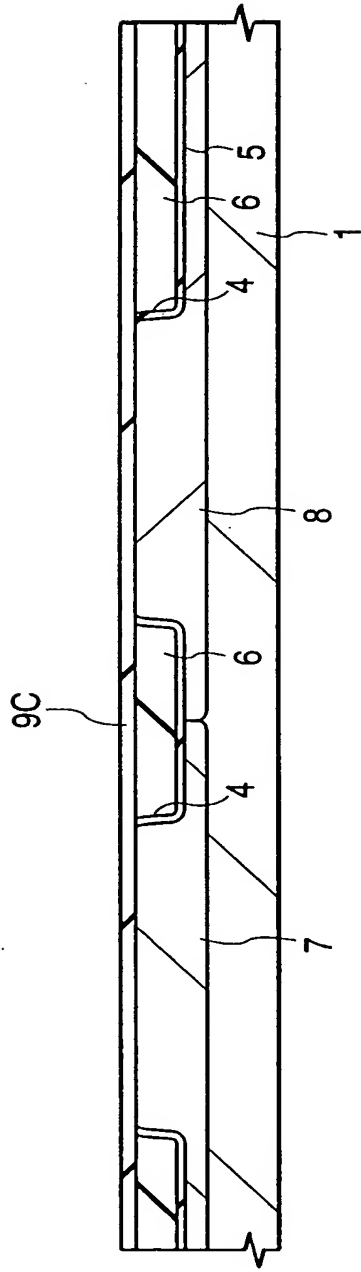


FIG. 29

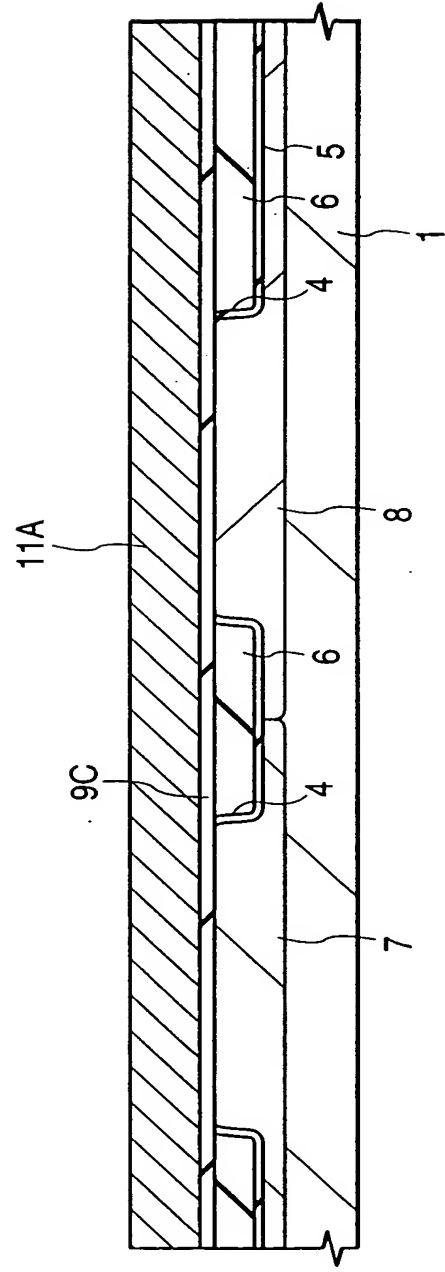


FIG. 30

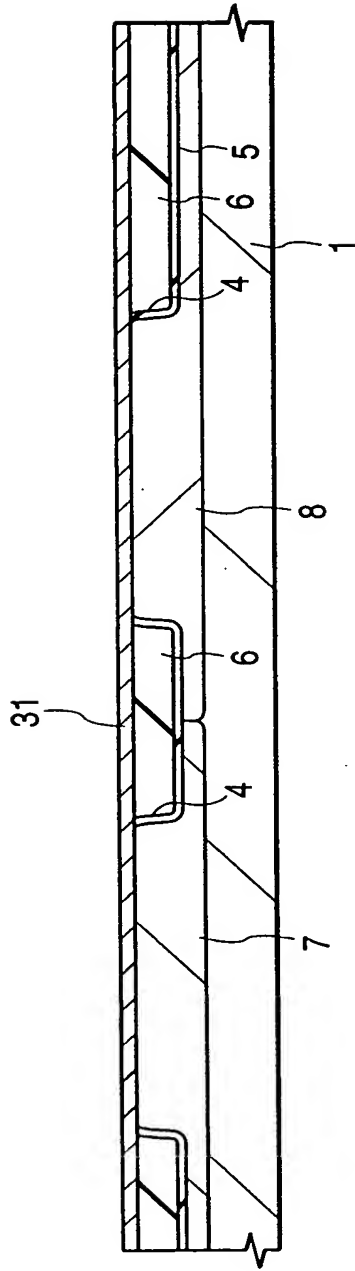


FIG. 31

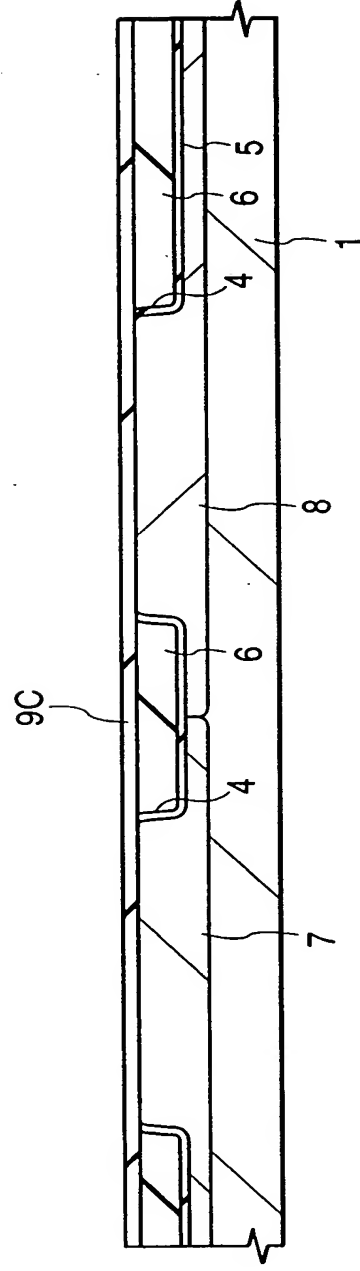


FIG. 32

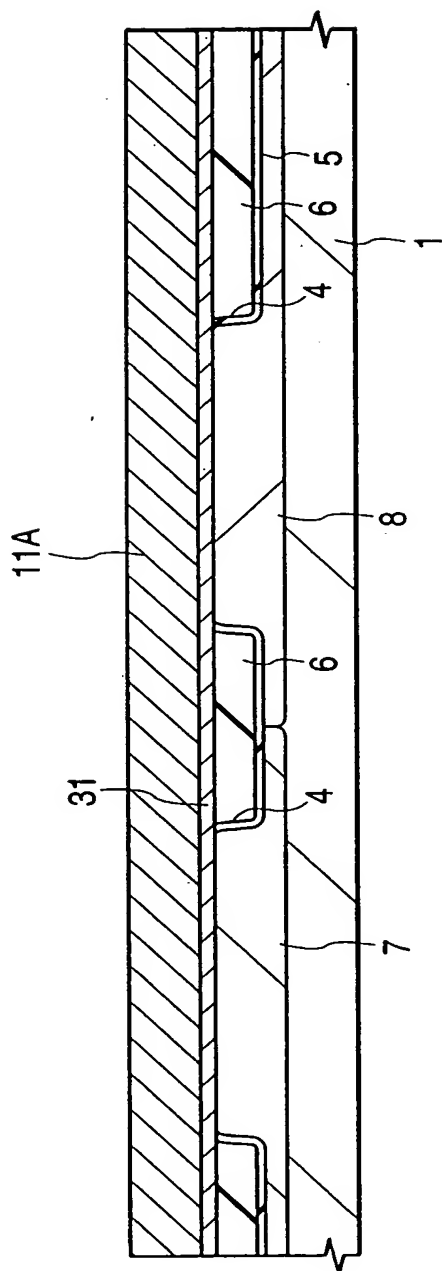


FIG. 33

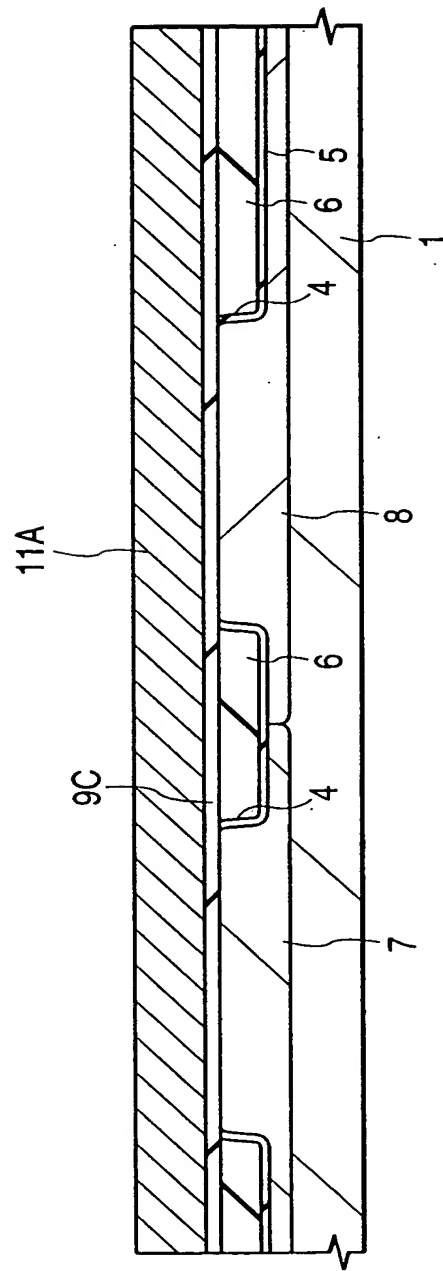


FIG. 34

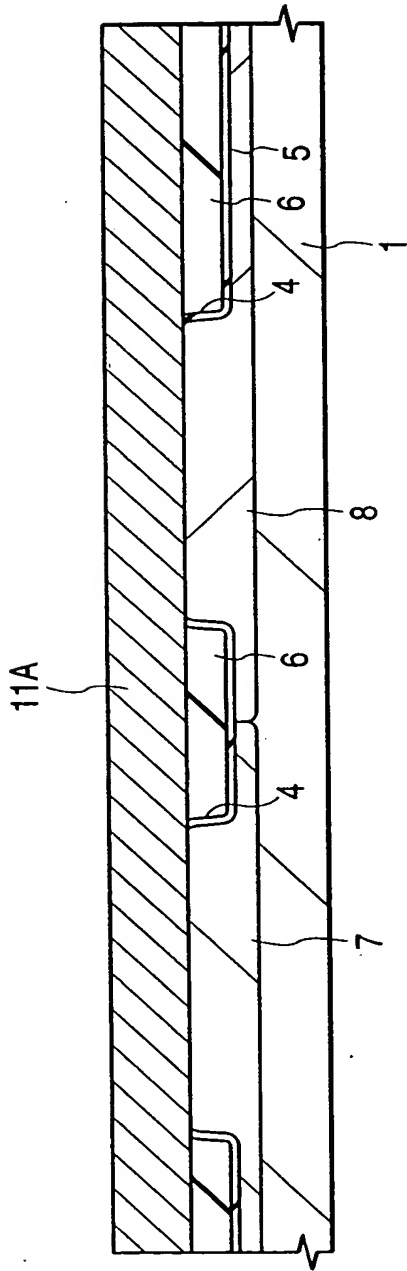


FIG. 35

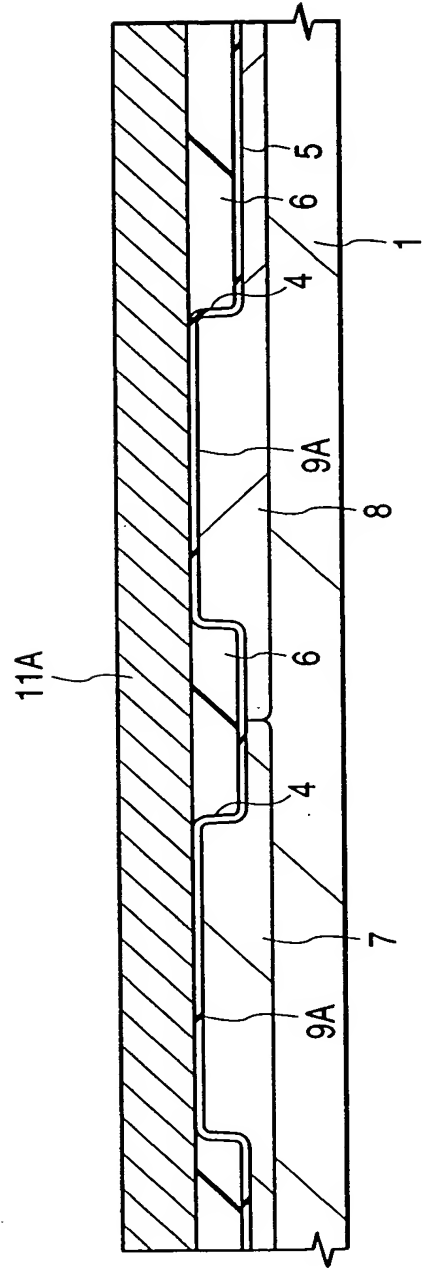


FIG. 36

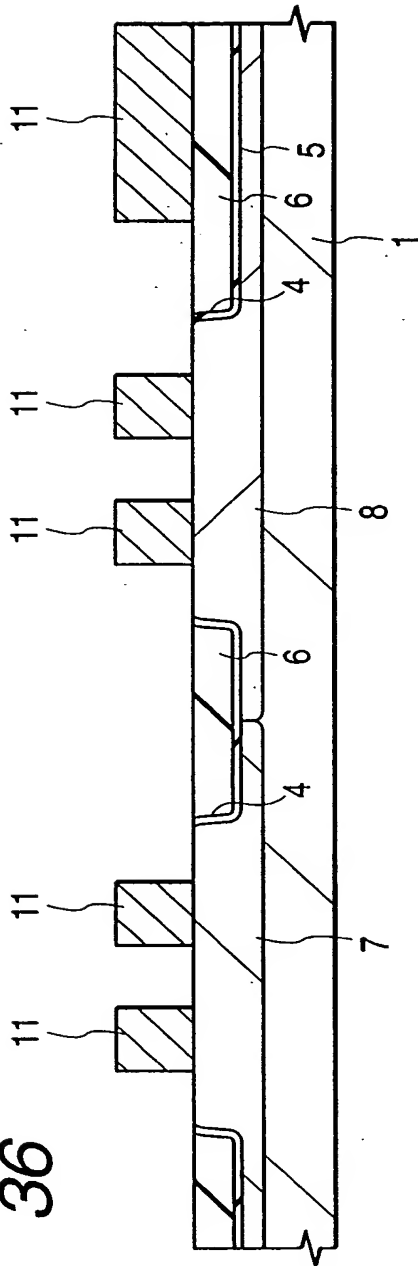


FIG. 37

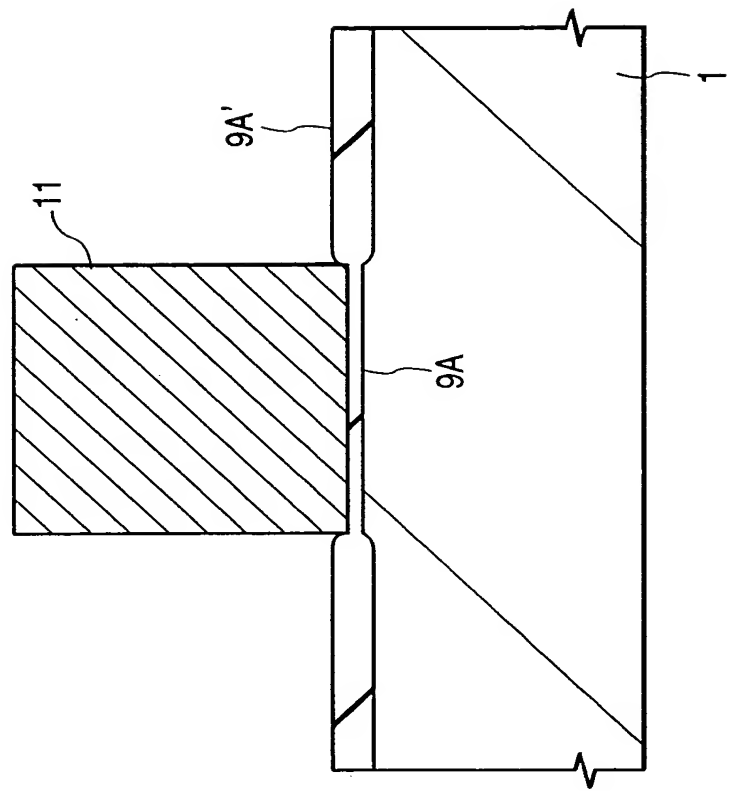


FIG. 38

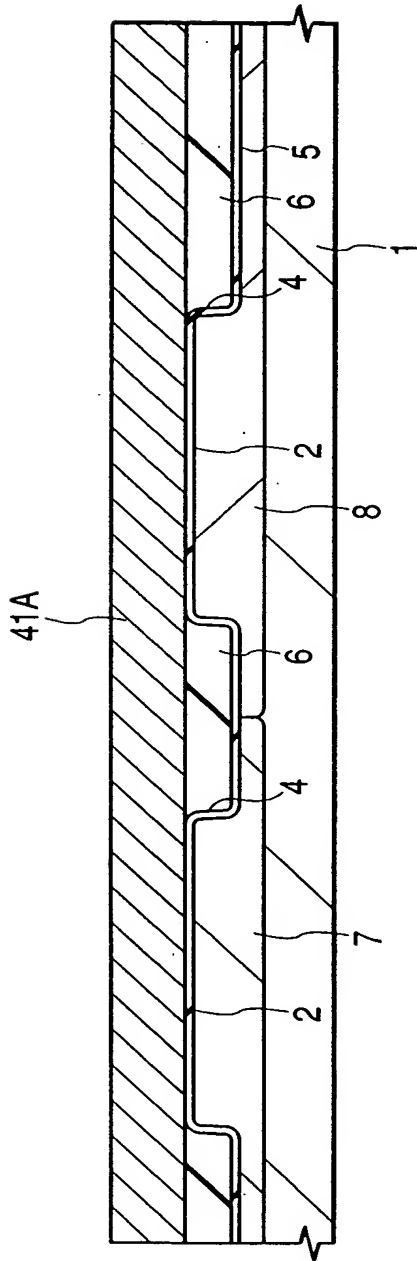


FIG. 39

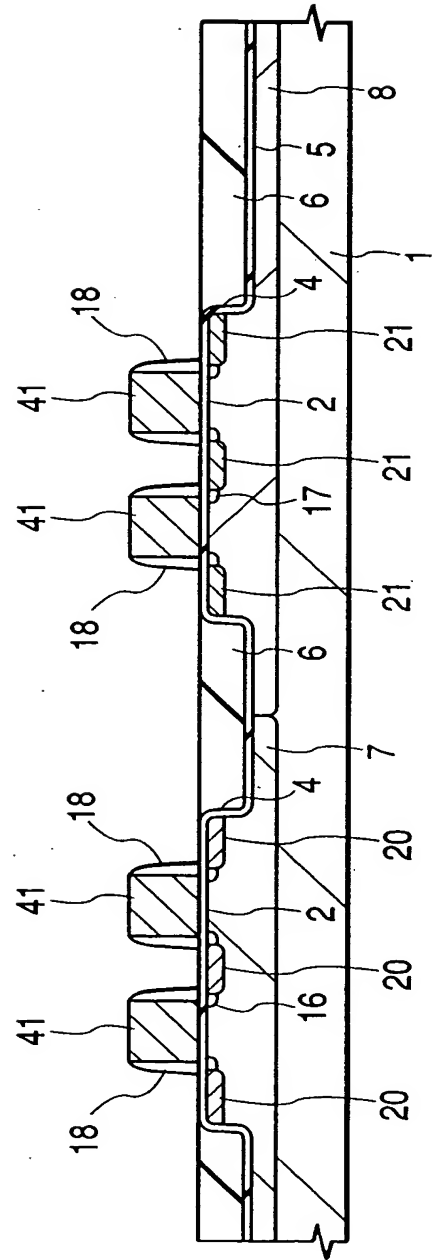


FIG. 40

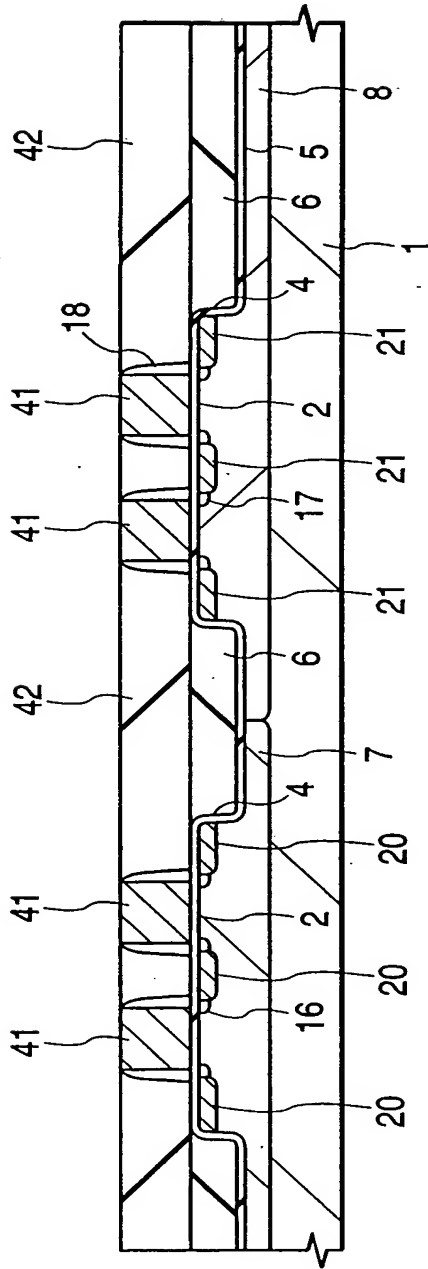


FIG. 41

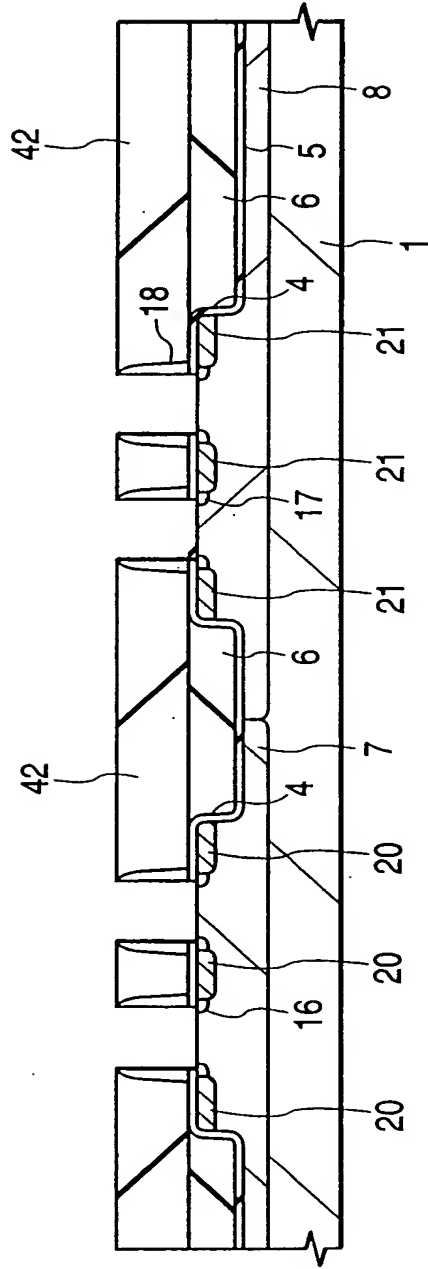


FIG. 42

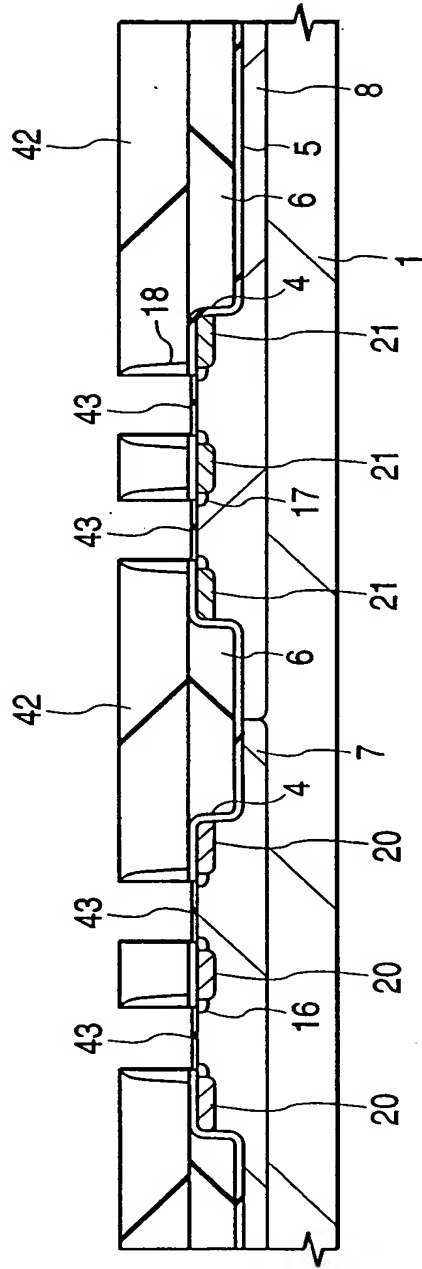


FIG. 43

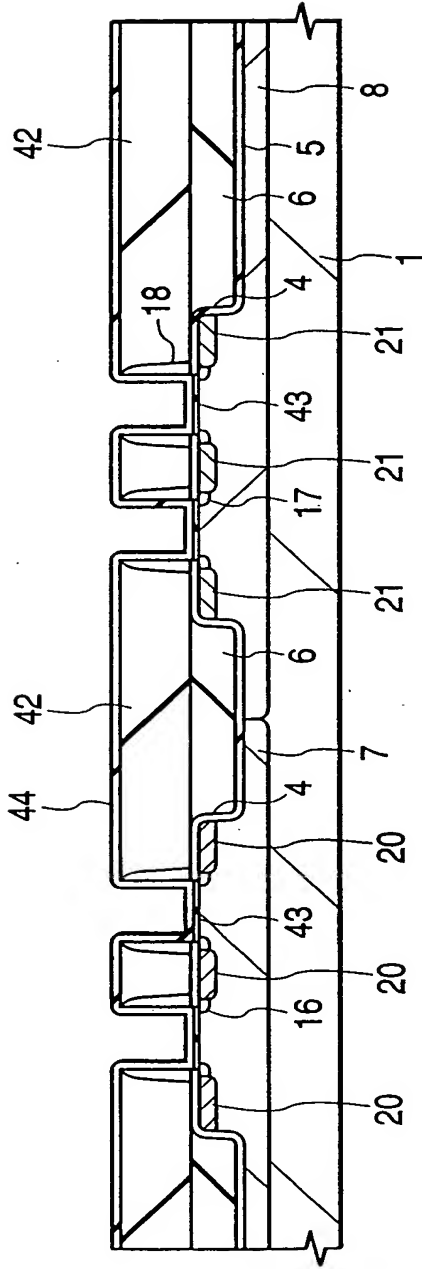


FIG. 44

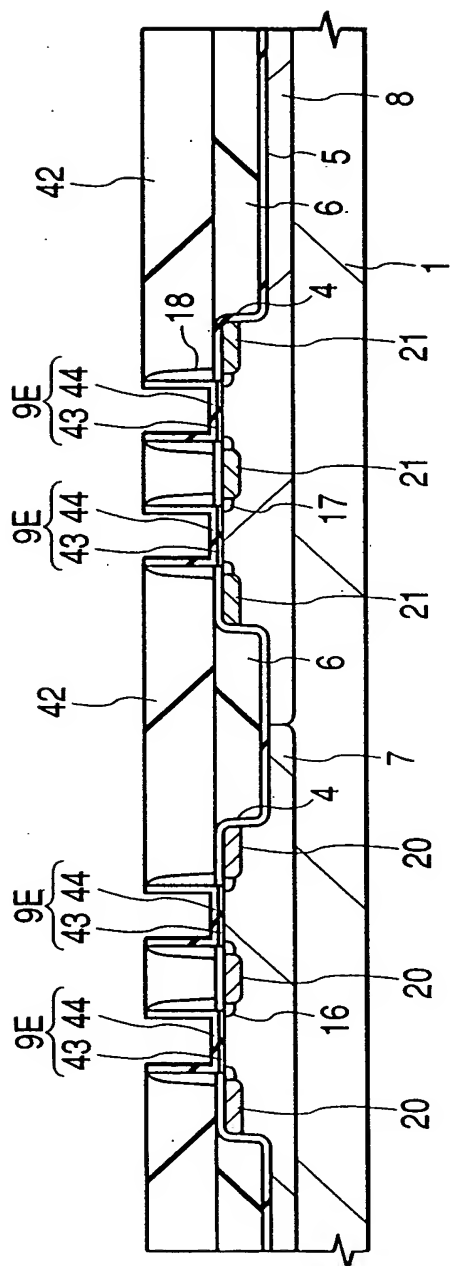


FIG. 45

